



NOTES

1. COATING(S1): LOW GDD COATING  
 $R_s > 99\% @ 710\text{ nm} - 900\text{ nm}, AOI = 45^\circ$   
 $R_p > 99\% @ 750\text{ nm} - 850\text{ nm}, AOI = 45^\circ$
2. GDD:  
 $|GDD_s| < 30\text{ fs}^2 @ 710\text{ nm} - 900\text{ nm}, AOI = 45^\circ$   
 $|GDD_p| < 30\text{ fs}^2 @ 750\text{ nm} - 850\text{ nm}, AOI = 45^\circ$
3. CLEAR APERTURE(S1, S2):  $> 90\% CA$
4. SURFACE QUALITY(S1, S2): 20/10(S/D)
5. SURFACE FLATNESS(S1):  $\lambda/4 @ 633\text{ nm}$
6. PARALLELISM(S1, S2):  $< 3\text{ arcmin}$
7. CHAMFER: 0.2 mm,  $45^\circ$
8. THICKNESS TOLERANCE:  $\pm 0.1\text{ mm}$
9. DIAMETER TOLERANCE:  $+0.0\text{ mm} / -0.1\text{ mm}$
10. BACK SURFACE (S2): POLISHED

DRAWING PROJECTION			<b>LBTEK</b>			
	NAME	DATE				
DRAWN	LZHOU	Aug./5th/24	ULTRAFAST MIRROR $\phi 50.8\text{ mm} \times 12\text{ mm}, 710\text{ nm} - 900\text{ nm}$			
APPROVAL	WCHENG	Aug./5th/24	MATERIAL	WEIGHT	SCALE	REV
FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES			UVFS	26.5 g	1:1	C